

CLAIM AMENDMENTS

1. (Currently Amended)

A method for forming a film

comprising a first process and a second process,

the first process comprising the steps of:

(i) supplying a discharge gas to a first discharge space of an atmospheric pressure plasma processing apparatus where high frequency electric field A is generated at atmospheric pressure or at approximately atmospheric pressure, whereby the discharge gas is excited;

(ii) transferring energy of the excited discharge gas to a film forming gas, whereby the film forming gas is excited; and

(iii) exposing a substrate to the excited film forming gas, whereby a film is formed on the substrate, and

the second process comprising the steps of:

(iv) supplying a gas containing an oxidizing gas to a second discharge space of the atmospheric pressure plasma processing apparatus where high frequency electric field B is generated at atmospheric pressure or at approximately atmospheric pressure, whereby the gas containing the oxidizing gas is excited; and

(v) exposing the film formed in the first process to the excited gas containing the oxidizing gas, and moving the substrate between the first discharge space and the second discharge space.

2. (Currently Amended)

A method for forming a film

comprising a first process and a second process,

the first process comprising the steps of:

(i) supplying a discharge gas to a first discharge space of an atmospheric pressure plasma processing apparatus where high frequency electric field A is generated at atmospheric pressure or at approximately atmospheric pressure, whereby the discharge gas is excited;

(ii) putting a film forming gas in contact with the excited discharge gas;

(iii) exposing a substrate to the film forming gas put in contact with the excited discharge gas, whereby a film is formed on the substrate, and

the second process comprising the steps of:

(iv) supplying a gas containing an oxidizing gas to a second discharge space of the atmospheric pressure plasma processing apparatus where high frequency electric field B is generated at atmospheric pressure or at approximately

atmospheric pressure, whereby the gas containing the oxidizing gas is excited; and

(v) exposing the film formed in the first process to the excited gas containing the oxidizing gas, and  
moving the substrate between the first discharge space and the second discharge space.

3. (Currently Amended)

A method for forming a film comprising a first process and a second process, the first process comprising the steps of:

(i) supplying gas 1 containing a film forming gas to a first discharge space of an atmospheric pressure plasma processing apparatus where high frequency electric field A is generated at atmospheric pressure or at approximately atmospheric pressure, whereby gas 1 is excited; and

(ii) exposing a substrate to excited gas 1, whereby a film is formed on the substrate, and

the second process comprising the steps of:

(iii) supplying gas 2 containing an oxidizing gas to a second discharge space of the atmospheric pressure plasma processing apparatus where high frequency electric field B is generated at atmospheric pressure or at approximately atmospheric pressure, whereby gas 2 is excited;

(iv) exposing the film formed in the first process to excited gas 2 containing the oxidization gas, and  
moving the substrate between the first discharge space  
and the second discharge space.

4. (Original)

The method of claim 3, wherein:

high frequency electric field A is formed by superposing a first high frequency electric field and a second high frequency electric field;

gas 1 contains a discharge gas and a reducing gas in addition to the film forming gas; and

the discharge gas contains nitrogen of which content is 50% by volume or more based on a volume of the discharge gas.

5. (Original)

The method of claim 4, wherein the reducing gas is hydrogen.

6. (Previously Presented)

The method of claim 4, wherein:

a discharge space of the first process is formed between a first electrode and a second electrode which are facing each other; and

the first high frequency electric field is applied by the first electrode and the second high frequency electric field is applied by the second electrode.

7. (Previously Presented)

The method of claim 6, wherein:

a frequency of the second high frequency electric field  $\omega_2$  is higher than a frequency of the first high frequency electric field  $\omega_1$ ;

intensity of the first high frequency electric field  $V_1$ , intensity of the second high frequency electric field  $V_2$ , and intensity of discharge starting electric field  $IV_1$  satisfy one of the formulas:

$V_1 \geq IV_1 > V_2$  and  $V_1 > IV_1 \geq V_2$ ; and

a power density of the second high frequency electric field is not less than  $1 \text{ W/cm}^2$ .

8. (Original)

The method of claim 7, wherein:

high frequency electric field B is formed by superposing a third high frequency electric field and a fourth high frequency electric field.

9. (Original)

The method of claim 8, wherein:

a discharge space of the second process is formed between a third electrode and a fourth electrode which are facing each other; and

the third high frequency electric field is applied by the third electrode and the fourth high frequency electric field is applied by the fourth electrode.

10. (Previously Presented)

The method of claim 9, wherein the first electrode and the third electrode are common.

11. (Original)

The method of claim 8, wherein:

a frequency of the fourth high frequency electric field  $\omega_4$  is higher than a frequency of the third high frequency electric field  $\omega_3$ ;

intensity of the third high frequency electric field V3, intensity of the fourth high frequency electric field V4, and intensity of discharge starting electric field IV2 satisfy one of the formulas:

$V3 \geq IV2 > V4$  and  $V3 > IV2 \geq V4$ ; and

a power density of the fourth high frequency electric field is not less than  $1W/cm^2$ .

12. (Original)

The method of claim 3, wherein the film is a metal oxide film.

13. (Original)

The method of claim 3, wherein the film is a transparent conductive film.

14. (Original)

The method of claim 3, wherein the film forming gas contains an organo-metallic compound having a metal atom selected from the group consisting of indium(In), tin(Sn), zinc(Zn), zirconium(Zr), antimony(Sb), aluminum(Al), gallium(Ga) and germanium(Ge).

15. (Original)

The method of claim 3, wherein the first process and the second process are alternately repeated a plurality of times.

16. (Original)

The method of claim 3, wherein a thickness of the accumulated film in the first process per batch is not more than 10 nm.

17. (Currently Amended)

A method for forming a film comprising a first process and a second process, the first process comprising the steps of:

(i) supplying gas 1 containing a film forming gas to a first discharge space of an atmospheric pressure plasma processing apparatus at atmospheric pressure or at approximately atmospheric pressure;

(ii) applying high frequency electric field A to the first discharge space, whereby gas 1 is excited; and

(iii) exposing a substrate to the excited gas 1 whereby a film is formed on the substrate, wherein

(a) the high frequency electric field A is formed by superposing a first high frequency electric field and a second high frequency electric field;

(b) a frequency of the second high frequency electric field  $\omega_2$  is higher than a frequency of the first high frequency electric field  $\omega_1$ ;

(c) intensity of the first high frequency electric field  $V_1$ , intensity of the second high frequency electric field  $V_2$ , and intensity of discharge starting electric field  $IV_1$  satisfy one of the following formulas:  
 $V_1 \geq IV_1 > V_2$  and  $V_1 > IV_1 \geq V_2$ ;

(d) a power density of the second high frequency electric field is not less than  $1 \text{ W/cm}^2$ ;

(e) gas 1 contains a reducing gas and a discharge gas;

(f) the discharge gas contains nitrogen of which content is 50% by volume or more based on a volume of a discharge gas in addition to the film forming gas; and

(g) the film forming gas contains an organo-titanium compound, and

the second process comprising the steps of:

(iv) supplying gas 2 containing an oxidizing gas to a second discharge space of the atmospheric pressure plasma

processing apparatus at atmospheric pressure or at approximately atmospheric pressure;

(v) applying high frequency electric field B to the second discharge space, whereby gas 2 is excited; and

(vi) exposing a substrate having thereon a film formed by gas 1 to excited gas 2, and

moving the substrate between the first discharge space and the second discharge space.

18. (Original)

The method of claim 17, wherein the reducing gas is hydrogen.

19. (Currently Amended)

The method of claim 17, wherein the first discharge space of the first process is formed between a first electrode and a second electrode which are facing each other; and

the first high frequency electric field is applied by the first electrode and the second high frequency electric field is applied by the second electrode.

20. (Currently Amended)

The method of claim 19, wherein:

high frequency electric field B is formed by superposing a third high frequency electric field and a fourth high frequency electric field.

21. (Currently Amended)

The method of claim 20, wherein:

the second discharge space of the second process is formed between a third electrode and a fourth electrode which are facing each other; and

the third high frequency electric field is applied by the third electrode and the fourth high frequency electric field is applied by the fourth electrode.

22. (Previously Presented)

The method of claim 21, wherein the first electrode and the third electrode are common.

23. (Original)

The method of claim 20, wherein:

a frequency of the fourth high frequency electric field  $\omega_4$  is higher than a frequency of the third high frequency electric field represented by  $\omega_3$ ;

intensity of the third high frequency electric field  
V3, intensity of the fourth high frequency electric field  
V4,

and intensity of discharge starting electric field IV2  
satisfy one of the following formulas:

$$V3 \geq IV2 > V4 \text{ and } V3 > IV2 \geq V4; \text{ and}$$

a power density of the fourth high frequency electric  
field is not less than 1 W/cm<sup>2</sup>.

24. (Original)

The method of claim 17, wherein the first process and  
the second process are alternately repeated a plurality of  
times.

25. (Original)

The method of claim 17, wherein a thickness of the  
film accumulated in the first process per time is not more  
than 20 nm.

26. (Original)

A substrate having thereon the film formed by the  
method of claim 3.